AP: Fashion Design—Apparel (See also AF, AR, DP, FD, FF, TL)

**AP 144 — Outerwear and Performance Apparel Sewing Techniques**
2.5 credits; 1 lecture and 3 lab hours
Produce outerwear garments in a sample-room setting using construction techniques specific to the outerwear and performance apparel market. Special focus is on the use of technically enhanced fabrics and protective design details in the construction of rainwear, urban outerwear, skiwear, and fishing, hiking, and boating apparel.
Prerequisite(s): DP 111 or FD 131 or TL 111 or MW 141 or approval of program advisor.

**AP 222 — Computer-Aided Flat Pattern Design**
1 credit; 2 lab hours
Through hands-on experience, learn computer-aided design for patternmaking and understand its creative potential.
Prerequisite(s): FD 121.

**AP 223 — Advanced Computer-Aided Flat Pattern Design**
2 credits; 1 lecture and 2 lab hours
Learn advanced features and capabilities of computer-aided design using the Lectra Modaris pattern design software. Using CAD, re-create the pattern designer’s traditional working environment by translating original ideas to the computer, digitizing and modifying designs, plotting out design creations, and managing the file information.
Prerequisite(s): AP 222 or approval of chairperson.

**AP 241 — Leather Apparel Design Room Techniques**
2.5 credits; 1 lecture and 3 lab hours
Teaches construction, processing, finishing, and decorative techniques for making men’s or women’s leather garments. Learn about the leather apparel industry, resources, and suppliers.
Prerequisite(s): MW 141 or FD 131.

**AP 242 — Haute Couture Sewing Techniques**
2.5 credits; 1 lecture and 3 lab hours
The sewing techniques practiced in the finest haute couture ateliers around the world are introduced and provide the basis for understanding couture. Learn couture techniques in cutting, hand stitching, seam and hem finishes, pocket construction, pressing, and finishing.
Prerequisite(s): AP 242 or approval of chairperson.

**AP 243 — Haute Couture Decorative Techniques and Embellishments**
2.5 credits; 1 lecture and 3 lab hours
Expands knowledge of the couture by exploring various decorative techniques. Learn how to hand bead and apply rocailles, sequins, pearls, and faux gems on different types of fabrics. Create embellishments such as flowers and frog closures from fabric and ribbons, hand embroider original designs, and learn the arts of quilting, cartridge pleating, and trapunto.
Prerequisite(s): AP 242 or approval of chairperson.

**AP 244 — Haute Couture Construction and Technology**
2.5 credits; 1 lecture and 3 lab hours
Apply couture sewing methodology and construct a skirt and jacket in order to understand the fitting process, couture fabric selection, proper cutting procedures, and inner construction methods.
Prerequisite(s): AP 242.
AP 253 — Leather Apparel Design
2.5 credits; 1 lecture and 3 lab hours
Study the use of leather, suede, and other animal skins and apply these materials to the design principles exclusive to creating men’s and women’s apparel. Develop original designs utilizing draping and flat pattern industrial methods.
Prerequisite(s): FD 112 and FD 221 and (AP 241 or MW 232).

AP 265 — Hand-Knit Design
2 credits; 1 lecture and 2 lab hours
Preparation for using hand-knitting machines to create original ideas for knitted fabrics and garments. Emphasizes using various stitch patterns and different textured yarns and colors to achieve new fabric textures.

AP 275 — Haute Couture Apparel Design
3 credits; 0 lecture and 6 lab hours
Apply knowledge of the couture to design, drape, fit, and construct a mini-collection for a particular target market. Develop styles and images through fabric sourcing, market research, and inspirational research.
Prerequisite(s): (DP 212 or FD 112) and AP 243 and AP 244.

AP 281 — Outerwear Apparel Design
2.5 credits; 1 lecture and 3 lab hours
Drawing on market research and trend services, create original men’s and women’s traditional, urban, or casual outerwear designs with a focus on the technical, functional, and aesthetic needs of the end user.
Prerequisite(s): (AP 144 and TS 171) and (FD 112 or FD 221 or DP 211 or MW 232).

AP 282 — Performance Apparel Design
2.5 credits; 1 lecture and 3 lab hours
Create performance apparel based on the principles of human physiology in extreme movement, and build on the technical and aesthetic needs of the serious outdoor sports enthusiast. Conduct market research and employ forecast services to develop designs.
Prerequisite(s): (AP 144 and TS 171) and (FD 112 or FD 221 or DP 211 or MW 232).

AP 322 — Apparel Product Data Management
2 credits; 1 lecture and 2 lab hours
Apply principles of product data management using web-based software. Emphasizes creating garment information and specifications at different stages of development from design to costing to manufacture. Execute style packages and line plans for sample development.
Prerequisite(s): AP 222 or PM 221 or approval of program advisor.

AP 337 — Primavision Apparel Design Development
2 credits; 1 lecture and 2 lab hours
Gain knowledge of technical line development and execution through the study and use of the software program Primavision, by Lectra Systems. Original concepts are translated into technical design factory packages ready for sample development. Emphasis is on specifications and construction details involved in woven and knit fabric development.
Prerequisite(s): FD 353 or approval of chairperson.

AP 351 — Experiencing Style
2 credits; 1 lecture and 2 lab hours
Photography students learn about the factors that influence the design and presentation of a collection. Working with Fashion Design students, they study the importance of the market, branding, trends, and the structure of the design house.
Prerequisite(s): PH 371.
AP 412 — AMERICAN COUTURE FASHION
4 credits; 1 lecture and 6 lab hours
Examines the fundamentals of couture and expensive ready-to-wear garments. Create one finished garment and two completely sewn garments in muslin, resulting in a coordinated toile mini collection using special techniques and fabrics characteristic of this market.

AP 421 — Computerized Pattern Design
2 credits; 1 lecture and 2 lab hours
Introduction to the operation of Gerber computer and Gerber pattern design system and development of abilities to efficiently create original ideas by computer. Includes discussion of hardware and patternmaking program.
Prerequisite(s): AP 222 and AR 213.

AP 422 — Advanced Computerized Pattern Design: Gerber AccuMark
2 credits; 1 lecture and 2 lab hours
Using software tools designed for advanced pattern design techniques, increase pattern design capabilities and learn how to combine computer automation with design tools for advanced pattern development.
Prerequisite(s): AP 421.